

Notice of References Cited	Application/Control No. 10/712,775	Applicant(s)/Patent Under Reexamination HAN ET AL.	
	Examiner Anita K. Alanko	Art Unit 1765	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,770,426 B1	08-2004	Vaartstra, Brian A.	430/331
	B	US-6,800,142 B1	10-2004	Tipton et al.	134/26
	C	US-2004/0198627 A1	10-2004	Masuda et al.	510/412
	D	US-6,715,498 B1	04-2004	Humayun et al.	134/1.3
	E	US-6,764,552 B1	07-2004	Joyce et al.	134/3
	F	US-6,871,656 B2	03-2005	Mullee, William H.	134/103.1
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Liu, F. et al "Use of phosphorus-31 (1+) for mask fabrication" Bandaoti Xuebao, 1984, 5(5) 573-6.
	V	Shibata, K. et al "Improvement of dry etching resistance of photoresist by means of ion implantation" IEIC Technical Report, 1995, Vol.95, No. 206, pp 51-57.
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.